## **Application Data Sheet**

## **Application Information**

Application Type:: Regular

Subject Matter:: Utility

Suggested Group Art Unit:: N/A

CD-ROM or CD-R?:: None

Sequence submission?:: None

Computer Readable Form (CRF)?:: No

Title:: METHOD FOR N+ DOPING OF

AMORPHOUS SILICON AND

POLYSILICON ELECTRODES IN DEEP

**TRENCHES** 

Attorney Docket Number:: INTECH 3.0-104

Request for Early Publication?:: No

Request for Non-Publication?:: No

Suggested Drawing Figure:: 1

Total Drawing Sheets:: 6

Small Entity?:: No

Petition included?:: No

Secrecy Order in Parent Appl.?:: No

## **Applicant Information**

Applicant Authority Type:: Inventor

Primary Citizenship Country:: Germany

Status:: Full Capacity

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Correspondence Customer Number::

000530

Representative Information

Representative Customer Number::

000530

**Assignee Information** 

Assignee name::

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Street of mailing address::

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City of mailing address::

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State or Province of mailing address::

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